MEMS Symposium Keynote to Highlight 3-D Optical Lithography

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SAN JOSE – Dr. Luke P. Lee will describe a new 3-D optical lithography for waveguides self-assembly in the MEMS Packaging Symposium keynote next month.

In the presentation, Lee, a professor in the University of California Berkeley department of Bioengineering, will reveal the process, which uses self-aligned microlenses and self-writing in photopolymers.

His talk takes place May 22 in San Jose.

After the keynote, Karen Lightman, managing director, MEMS Industry Group, will present findings and recommendations from the MEMS Industry Group members' annual meeting.

Symposium segments include consumer, automotive, biomedicine, and WLPs and 3-D ICs, among others.

To register, visit www.meptec.org.